

Supporting Information

In-vacuo detection of Ti hydride using advanced XPS technique

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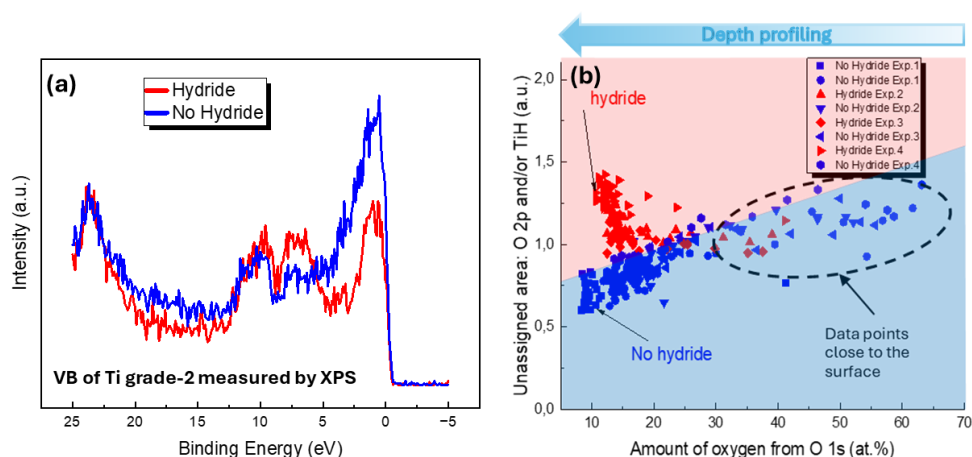


Figure: (a) Valence bands spectra of two Ti grade-2 samples with and without presence of hydride, measured after sputtering ~55(nm, SiO₂ equivalent) (b) The data plotted between the atomic percentage of O 1s and the area under the O2p/TiH peak with respect to depth.